

L Number	Hits	Search Text	DB	Time stamp
1	483	sputtering same (inline in-line)	USPAT	2003/03/11 08:22
2	79	sputtering same (inline in-line) same (conventional well-known (well adj known))	USPAT	2003/03/11 08:51
3	3	spf-530h	USPAT	2003/03/11 08:51
4	0	spf-530h same (inline in-line)	USPAT	2003/03/11 09:18
5	72	(crystal near size) same (sputtering)	USPAT	2003/03/11 09:18
-	2	jp-08225936-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/15 16:07
-	13553	jp-08225936-\$.did.MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/15 16:14
-	13553	jp-08225936-\$.did.MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/15 16:15
-	13551	MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 08:49
-	4	((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank)) and (substrate support) and (helium "He")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:08
-	25	(MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:06
-	22	(photomask adj blank) and (substrate support) and (helium "He")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/28 15:17
-	603	(photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 11:00
-	63	((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/28 15:16
-	3548	(antireflective ARC) same (chromium adj nitride Cr?N?)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 11:22
-	744	sputtering same (("ar" argon) and (helium "He"))	USPAT; US-PGPUB	2001/08/16 11:57
-	60	((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)) not ((photomask adj blank) and (substrate support) and (helium "He"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 12:38
-	263296	(430/5 430/322 430/320 428/\$ 427/\$).CCLS.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 12:41
-	139	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?\$) AND (SPUTTER SPUTTERING SPUTTERED)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 12:49
-	260869	HE?\$(HEADLEY-J-L)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 12:48
-	702	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (SPUTTER SPUTTERING SPUTTERED)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 12:49

-	442	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?\$5) AND (SPUTTER SPUTTERING SPUTTERED)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 12:52
-	449	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?\$3) AND (SPUTTER SPUTTERING SPUTTERED)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 12:58
-	80	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"? ) AND (SPUTTER SPUTTERING SPUTTERED)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/28 15:16
-	73	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"? ) AND (SPUTTER SPUTTERING SPUTTERED) ) NOT ((photomask adj blank) and (substrate support) and (helium "He"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2001/08/16 13:07
-	92	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"? ) AND (SPUTTER SPUTTERING SPUTTERED)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:05
-	78	((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:05
-	30	(photomask adj blank) and (substrate support) and (helium "He")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:05
-	1	ep-1022614-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/28 15:25
-	1	("5830332").PN.	USPAT	2002/03/28 15:26
-	16	("3840451"   "4417946"   "4486286"   "4529475"   "4551216"   "4620898"   "4624736"   "4684436"   "4822466"   "4851097"   "4913789"   "4973345"   "5045165"   "5073241"   "5122249"   "5429730").PN.	USPAT	2002/03/28 15:26
-	1	("4720442").PN.	USPAT	2002/03/28 15:36
-	5	("4363846"   "4374912"   "4497878"   "4530891"   "4563407").PN.	USPAT	2002/03/28 15:43
-	5	("4363846"   "4374912"   "4497878"   "4530891"   "4563407").PN.	USPAT	2002/03/28 15:51
-	13	4720442.URPN.	USPAT	2002/03/28 15:52
-	37	((((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"? ) AND (SPUTTER SPUTTERING SPUTTERED) ) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) ((photomask adj blank) and (substrate support) and (helium "He") ) ) and @pd>=20010731	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/28 16:19
-	331	(sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/28 16:20
-	13	((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:05
-	626	("He" Helium) same (chromium)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2002/03/28 16:35

-	28	((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:05
-	3	gb-2325473-\$.did. or ep-605814-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 12:12
-	93	((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:05
-	118	((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"? ) AND (SPUTTER SPUTTERING SPUTTERED)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:06
-	32	((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:06
-	16	((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:07
-	47	(photomask adj blank) and (substrate support) and (helium "He")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:07
-	8	((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank)) and (substrate support) and (helium "He")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:07
-	31	((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:07
-	26299	tensile adj stress	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:09
-	9	((gb-2325473-\$.did. or ep-605814-\$.did. ) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"? ) AND (SPUTTER SPUTTERING SPUTTERED) ) (((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack) ) ((photomask adj blank) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank)) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (tensile adj stress))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:46

-	56	((gb-2325473-\$.did. or ep-605814-\$.did. ) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) ) (((He" Helium) same (chromium)) and (blank photomask adj blank photoblank) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank) ) ((photomask adj blank) and (substrate support) and (helium "He") ) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (deposition adj rate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/05 13:46
-	51	((gb-2325473-\$.did. or ep-605814-\$.did. ) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) ) (((He" Helium) same (chromium)) and (blank photomask adj blank photoblank) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank) ) ((photomask adj blank) and (substrate support) and (helium "He") ) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (deposition adj rate)) not (((gb-2325473-\$.did. or ep-605814-\$.did. ) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) ) (((He" Helium) same (chromium)) and (blank photomask adj blank photoblank) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblank) ) ((photomask adj blank) and (substrate support) and (helium "He") ) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (tensile adj stress))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:33
-	0	605814.URPN.	USPAT	2003/03/06 10:04
-	0	605814.URPN.	USPAT	2003/03/06 10:05

-	4	((("4663183") or ("4728529"))).PN.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:21
-	252	flatness adj degree	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:22
-	4975	(blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 12:47
-	3	((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (flatness adj degree)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:23
-	154	((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (tensile near stress)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:27
-	571552	(transition near metal) (chromium "Cr" )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:32
-	60	((((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (tensile near stress) ) and ((transition near metal) (chromium "Cr" ))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:33

-	52	(((gb-2325473-\$.did. or ep-605814-\$.did. ) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPATTERED) ) (((He" Helium) same (chromium)) and (blank photomask adj blank photoblack) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack) ) ((photomask adj blank) and (substrate support) and (helium "He") ) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (deposition adj rate)) not (((gb-2325473-\$.did. or ep-605814-\$.did. ) (((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPATTERED) ) (((He" Helium) same (chromium)) and (blank photomask adj blank photoblack) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack) ) ((photomask adj blank) and (substrate support) and (helium "He") ) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (tensile adj stress))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 10:35
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-	60	(((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (tensile near stress) ) and ((transition near metal) (chromium "Cr" ))) not (((("4663183") or ("4728529")).PN.) ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")) and (flatness adj degree)) (((gb-2325473-\$.did. or ep-605814-\$.did. ) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) ) (((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack) ) ((photomask adj blank) and (substrate support) and (helium "He") ) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank)) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (deposition adj rate)) not (((gb-2325473-\$.did. or ep-605814-\$.did. ) ((photomask blank phototool) and (substrate support) and (helium "He") and (sputter sputtering sputtered)) and (thin adj film) and (vacuum adj chamber) ) (((430/5 430/322 430/320 428/\$ 427/\$).CCLS.) AND (PHOTOMASK MASK) AND ((SUBSTRATE SUPPORT) NEAR TRANSPARENT) AND (HELIUM "HE"?) AND (SPUTTER SPUTTERING SPUTTERED) ) (((("He" Helium) same (chromium)) and (blank photomask adj blank photoblack) ) (((sputtering) same (helium "He") same (nitrogen "N2" "N.sub.2")) and (blank photomask adj blank photoblack) ) ((photomask adj blank) and (substrate support) and (helium "He") ) (((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank)) and (substrate support) and (helium "He") ) ((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (photomask adj blank) )) and (tensile adj stress)))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 12:23
-	150556	(tensile adj stress ) (warp warping flatness)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 12:23
-	6812	((tensile adj stress ) (warp warping flatness)) and (sputtering)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 12:24
-	457	(((tensile adj stress ) (warp warping flatness)) and (sputtering)) and ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He"))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 12:25
-	432	(((tensile adj stress ) (warp warping flatness)) and (sputtering)) and ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He"))) and (metal (transition near metal) chromium chrome "Cr")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 12:48

-	5873	430/5.ccls.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 12:48
-	16	430/5.ccls. and (((((tensile adj stress ) (warp warping flatness)) and (sputtering)) and ((blank photomask mask) and (thin adj film) and (substrate support) and (helium "He")))) and (metal (transition near metal) chromium chrome "Cr" ) )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 15:34
-	41	(dc.m/c. adj power) near source	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 15:54
-	19876	power adj density	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 15:55
-	28	(power adj density) same (sputter adj target)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 16:40
-	0	(dc.m/c. adj bias adj potential) same (graphite near target) same ("W" watts watt)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 16:50
-	408	(dc.u/c. adj power adj source) same ("W" watts watt)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/06 16:57
-	15071	MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 09:16
-	1239	ROSASCO ROSASCO-S ROSASCO-STEPHAN ROSASCO-STEPHEN ROSASCO-STEPHEN-D ROSASCO-STEVE ROSASCO-STEVEN	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 08:59
-	18	(MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (ROSASCO ROSASCO-S ROSASCO-STEPHAN ROSASCO-STEPHEN ROSASCO-STEPHEN-D ROSASCO-STEVE ROSASCO-STEVEN)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 08:59
-	390	(MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (helium "He")	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 09:17
-	591	(MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (helium "He" (inert adj gas))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 09:17
-	191	((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (helium "He" ) and (metal )	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 09:18
-	66	((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (helium "He" ) and (metal ) and target	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 09:18
-	4	((MITSUI-MASARU YAMAGATA YAMAGATA-H YAMAGATA-HARUKI YAMAGATA-HARUYOSHI USHIDA USHIDA-M USHIDA-MASAO ) and (helium "He" ) and (metal ) and target) and (vacuum near chamber)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 10:22
-	16095	sccm	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 10:25



-	7	(direct adj current adj sputter) same (vacuum inline in-line chamber power)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 10:27
-	20	(direct adj current adj sputter) and (vacuum inline in-line chamber power)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 11:55
-	13	((direct adj current adj sputter) and (vacuum inline in-line chamber power)) not	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 11:55
-	249	((direct adj current adj sputter) same (vacuum inline in-line chamber power)) ((tensile adj stress) (flatness near degree)) same (helium He (inert))	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 12:46
-	19876	(power adj density) same (power)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 12:47
-	12	((power adj density) same (power) ) same (graphite adj target)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 15:47
-	2	(cm2) same (graphite adj target)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 13:04
-	75	(cm2 cm inch in2 centimeter meter) same (graphite adj target)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 13:05
-	2	jp-11012730-\$.did.	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 15:08
-	1298	(silicon adj wafer) same transparent	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 15:12
-	3	spf-530H	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 16:16
-	325	(sputtering adj power) same (rate)	USPAT; US-PGPUB; EPO; JPO; DERWENT	2003/03/10 16:19
-	249	(sputtering adj power) same (rate)	USPAT	2003/03/11 08:20